

DOCKET NO: 283053US0PCT

IN THE UNITED STATES PATENT & TRADEMARK OFFICE

IN RE APPLICATION OF :  
HARUO IWASAWA, ET AL. : EXAMINER: MOORE, M. G.  
SERIAL NO: 10/560,527 :  
FILED: DECEMBER 13, 2005 : GROUP ART UNIT: 1796  
FOR: SILANE POLYMER AND METHOD :  
FOR FORMING SILICON FILM

RESPONSE TO THE REQUIREMENT FOR RESTRICTION

COMMISSIONER FOR PATENTS  
ALEXANDRIA, VIRGINIA 22313

SIR:

In response to the Requirement for Restriction mailed February 12, 2008, Applicant's elect, without traverse, Group I: Claims 1 and 7-10 drawn to a polysilane.

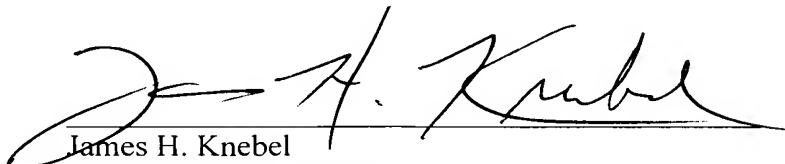
Applicants respectfully submit that the above-identified application is now in condition for examination on the merits, and early notice of such action is earnestly solicited.

Respectfully submitted,

OBLON, SPIVAK, McCLELLAND,  
MAIER & NEUSTADT, P.C.  
Norman F. Oblon

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